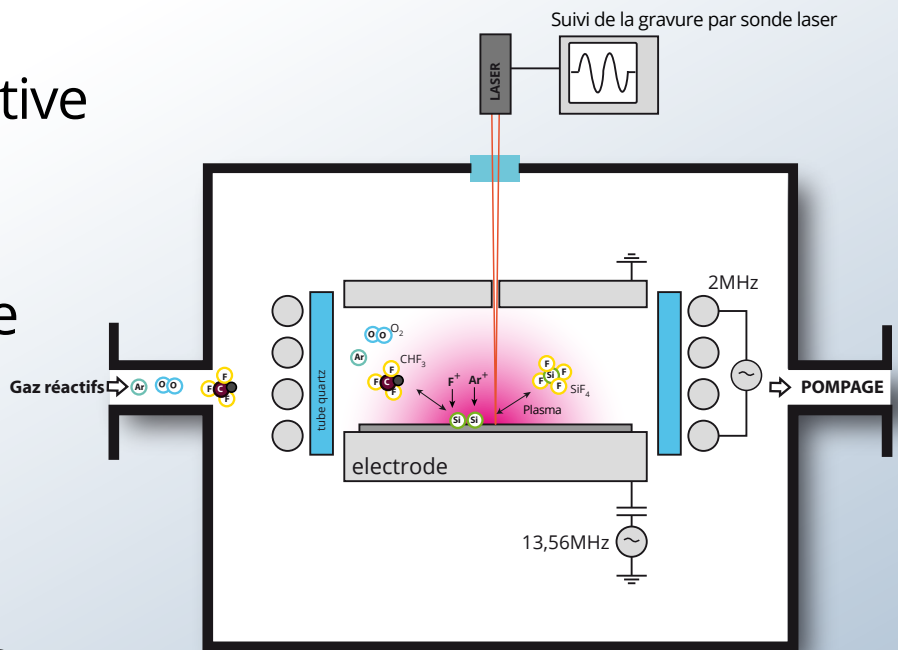


# Gravure ICP RIE

## Gravure ionique réactive

*Inductive Coupled Plasma  
Reactive Ion Etching*

## Technique de gravure sèche par plasma



### → Effet physique :

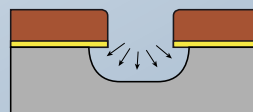
bombardement de gaz ionisés

### → Effet chimique :

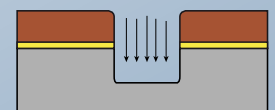
Gaz fluorés (gravure du Si)

Gaz chlorés (gravure des métaux et III-V)

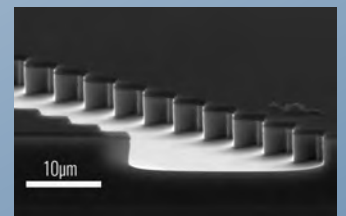
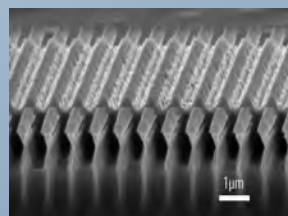
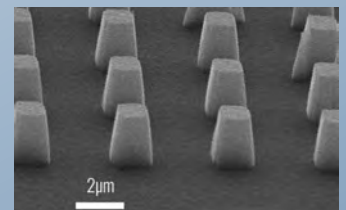
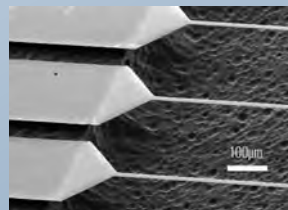
### → Contrôle de la gravure



isotrope



anisotrope



## Equipements



ICP RIE Chlorée  
Oxford plasmalab 100



ICP RIE fluorée  
Corial 200 IL



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